



## **Dr. Nahee Park**

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Nahee Park, Ph.D. has been Regional Development Apps (RDA) Engineer position at KLA Corp. and has researched the imaging-based overlay metrology in advanced device node circuits while collaborating with SK Hynix, Samsung electronics, Micron technology, Intel Corp., and IBM Corp., since September 2020. She received a Ph.D degree in Science from Sungkyunkwan University (SKKU), South Korea in August 2020 where she studied electrical properties of two-dimensional materials on functional substrates in field-effect transistor system for ferroelectric memory devices, interfacial phenomena study, and fabrication process development on new hybrid structures during integrated M.S.-Ph.D course. Her current research interest is optical metrology development for advanced device process control in semiconductor industry.